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(11) **EP 0 594 180 B1**

(12) **EUROPEAN PATENT SPECIFICATION**

(45) Date of publication and mention
of the grant of the patent:
10.12.1997 Bulletin 1997/50

(51) Int Cl.⁶: **G01L 1/12, G01B 7/24**

(21) Application number: **93117098.9**

(22) Date of filing: **21.10.1993**

(54) **A mechanical sensor**

Ein mechanischer Sensor

Une sonde mécanique

(84) Designated Contracting States:
DE FR GB IT

(30) Priority: **21.10.1992 JP 282663/92**

(43) Date of publication of application:
27.04.1994 Bulletin 1994/17

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Description

BACKGROUND OF THE INVENTION

1. Field of the Invention:

The present invention relates to a mechanical sensor, and more particularly to a mechanical sensor capable of detecting with high sensitivity, stress or strains.

2. Description of the Related Art:

In recent years, under the circumstances that electronic equipment is made smaller and thinner, there is a great demand for further miniaturization of mechanical sensors used in electronic equipment. A mechanical sensor utilizing a stress-magnetic effect has been put into practical use (e.g., see SAE Technical Paper Series 920700). Such a mechanical sensor is formed of a cylinder, to which an amorphous magnetic ribbon having a positive magnetostriction constant adheres, and detects the change of the permeability of the amorphous magnetic ribbon due to the stress applied thereto, by using a solenoidal coil.

The above-mentioned conventional mechanical sensor has a coil made of a conductive line with a diameter of about 20 to 30 μm , wound in a solenoidal shape and a magnetic bulk having a thickness of about 20 to 30 μm .

The above-mentioned conventional mechanical sensor has the following problems: Since such a mechanical sensor has a solenoidal coil and a magnetic bulk, it is difficult to miniaturize and integrate the sensor. In addition, since the thickness of the magnetic layer is in the range of 20 to 30 μm , and the diameter of the conductive line is in the range of 20 to 30 μm , there is a limit to the frequency of the sensor.

An example of a planar mechanical sensor suitable for the miniaturization is a strain gauge using a metallic foil. The sensitivity of the strain gauge is one-thousandth or less of that of the mechanical sensor utilizing a stress-magnetic effect.

DE 41 17 878 A1 discloses a planar magnetic element comprising a substrate and a first magnetic layer disposed thereon, an insulating layer disposed above the first magnetic layer, a planar coil consisting of a single conductor having a plurality of windings, which is disposed above the first insulating layer, a second insulating layer disposed above the planar coil, and a second magnetic layer disposed above the second insulating layer. This device can be used as an inductance device or a transformer.

EP 0 329 479 A2 discloses a strain gauge including a pair of coils printed on one face of a substrate and an amorphous magnetic metallic plate arranged on the other face of said substrate, having a magnetostrictive effect. Magnetic flux is generated by one of the paired coils and passes through the amorphous magnetic metallic

plate and links with the other of the coils. If a load is added to an object to be measured and strain of the object is caused by the load added, the magnetic permeability of the amorphous magnetic metallic plate is changed, due to the magnetostrictive effect, in response to the added load. The density of the magnetic flux passing through the magnetic metallic plate is also changed responsive to this changing magnetic permeability and composite inductance of the paired coils is then changed responsive to the changing density of the magnetic flux. The strain gage outputs a detection signal, which represents the changing density of the magnetic flux, thereby measuring the load added.

SUMMARY OF THE INVENTION

The mechanical sensor of this invention, includes:

- a magnetic layer having permeability which is changed in accordance with stress generated therein;
 - a coil having at least two terminals, allowing an electric current to flow therebetween to generate a magnetic flux, thereby magnetizing the magnetic layer; and
 - a substrate integrally supporting the magnetic layer and the coil,
- wherein the coil is a planar coil including at least one winding, each winding having a U-shaped portion formed of a first conductive line portion, a second conductive line portion, and a connecting portion connecting the first and second conductive line portions, the first and second conductive line portions extending in a first direction, the connecting portion extending in a second direction being vertical to the first direction, and impedance between the terminals is changed in accordance with a change of inductance caused by a change of the permeability of the magnetic layer,
- wherein the total length of each linear conductive line portion extending in the first direction is larger than the total length of each linear conductive line portion extending in the second direction; and the magnetic layer is magnetized substantially in a direction orthogonal to the first direction.

In one embodiment of the present invention, the coil is a planar coil including at least two windings, and a distance between conductive line portions in which an electric current flows in the same direction is smaller than a distance between conductive line portions in which an electric current flows in the opposite directions to each other.

In still another embodiment of the present invention, the coil is formed on an insulator layer supported by the substrate.

In still another embodiment of the present invention, the magnetic layer is formed between the insulator layer

and the substrate.

In still another embodiment of the present invention, the magnetic layer is formed on the coil with another insulator layer formed therebetween.

In still another embodiment of the present invention, the magnetic layer has a two-layered structure and sandwiches the coil.

In still another embodiment of the present invention, the mechanical sensor includes further a second U-shaped portion formed of a third conductive line portion, a fourth conductive line portion, and a connecting portion connecting the third and fourth conductive line portions, the first, second, third, and fourth conductive line portions extending in a first direction; and

wherein the first and second U-shaped portions are connected in series between the terminals.

Thus, the invention described herein makes possible the advantage of providing a mechanical sensor with high sensitivity capable of being made small, thin, and integrated.

This and other advantages of the present invention will become apparent to those skilled in the art upon reading and understanding the following detailed description with reference to the accompanying figures.

BRIEF DESCRIPTION OF THE DRAWINGS

Figure 1 is a partially perspective plan view showing a mechanical sensor of the present invention.

Figure 2 is a cross-sectional view taken along a line A-A' of Figure 1.

Figure 3 is a cross-sectional view taken along a line B-B' of Figure 1.

Figure 4 is a perspective view showing another mechanical sensor of the present invention.

Figure 5 is a cross-sectional view taken along a line G-G' of Figure 4.

Figure 6 is a partially perspective plan view showing still another mechanical sensor of the present invention.

Figure 7 is a cross-sectional view taken along a line J-J' of Figure 6.

Figure 8 is a cross-sectional view taken along a line K-K' of Figure 6.

Figures 9A through 9C show examples of planar coils used in the mechanical sensors of the present invention.

Figures 10A through 10C show examples of planar coils used in the mechanical sensors of the present invention.

Figures 11A and 11B show examples of planar coils used in the mechanical sensors of the present invention.

DESCRIPTION OF THE PREFERRED EMBODIMENTS

Hereinafter, the present invention will be described by way of illustrative examples with reference to the drawings.

Example 1

Figure 1 is a plan view showing the structure of a mechanical sensor of the present invention. Figure 2 is a cross-sectional view taken along a line A-A' of Figure 1, and Figure 3 is a cross-sectional view taken along a line B-B' of Figure 1.

Hereinafter, the structure of the mechanical sensor of the present example will be described with reference to these figures.

Referring to Figure 2, the cross-sectional structure of the mechanical sensor will be described. A magnetic layer 12a having a thickness of 5 μm is formed on a substrate 11 made of phosphor bronze, having a thickness of 0.5 mm. The substrate 11 can be made of any non-magnetic substance. The substrate 11 can be cylindrical, instead of being in a planar shape as shown in Figure 2. The magnetic layer 12a is made of an Fe based amorphous film formed by a sputtering method and contains Fe, Cr, Si, and B. The relative permeability and magnetostriction constant of the magnetic layer 12a at a frequency of 1 MHz are 100 and +22 ppm, respectively.

On the magnetic layer 12a, an insulator layer 13a made of SiO_2 , having a thickness of 2 μm is formed. On the insulator layer 13a, a planar coil 14 made of an aluminum film having a thickness of 5 μm and input/output terminals 15a and 15b (not shown in Figure 2) are formed.

The input/output terminals 15a and 15b are applied with a predetermined AC voltage, whereby an electric current flows through the planar coil 14. In the present specification, any each portion of the conductive line is called a line segment. The line segment is not limited to a linear shape, unless otherwise stated. In the planar coil 14, the minimum distance between conductive line portions (i.e., line segments), which are adjacent to each other and in which an electric current flows in the same direction, is 10 μm . More specifically, each distance between conductive line portions 14a and 14b, between conductive line portions 14c and 14d, between conductive line portions 14e and 14f, and between conductive line portions 14g and 14h is 10 μm . The minimum distance between the conductive line portions in which an electric current flows in the opposite directions to each other is 180 μm (see Figure 1). More specifically, each distance between the conductive line portions 14b and 14c, between the conductive line portions 14d and 14e, and between the conductive line portions 14f and 14g is 180 μm . An insulator layer 16 having the same thickness as that of the planar coil 14 fills between the conductive line portions in which an electric current flow in the same direction.

On the insulator layer 13a, another insulator layer 13b is formed so as to cover the planar coil 14. The insulator layer 13b (thickness: 2 μm) is made of the same material as that of the insulator layer 13a. The insulator layer 13b fills gaps between any conductive line portions

in which an electric current flows in the opposite directions to each other. On the insulator layer 13b, another magnetic layer 12b is formed. The magnetic layer 12b (thickness: 5 μm) is made of the same material as that of the magnetic layer 12a. In this way, in the present example, the planar coil 14 is sandwiched between the magnetic layers 12a and 12b.

Referring to Figure 1, the planar structure of the mechanical sensor will be described. The substrate 11 has a rectangular shape with a longitudinal side of 30 mm and a vertical side of 15 mm. The planar coil 14 is formed in a rectangular region on the substrate 11, the rectangular region having a length C of 3000 μm in a first direction F and having a width D of 820 μm in a second direction E which is vertical to the first direction F. As shown in Figure 1, the planar coil 14 of the present example has a basic structure including two windings on a plane (i.e., a double spiral structure). More specifically, the planar coil 14 has a basic structure in which each of the two windings of the planar coil 14 has first and second U-shaped portions connected in series. Each of the first U-shaped portions has first and second linear conductive line portions extending along the first direction F and a connecting portion connecting the first and second linear conductive lines. Likewise, each of the second U-shaped portions has third and fourth linear conductive line portions extending along the first direction F and a connecting portion connecting the third and fourth linear conductive line portions. Alternatively, it is considered that each of the second and third linear conductive line portions and the connecting portions connecting each of the second and third linear conductive line portions form other U-shaped portions extending in the direction opposite to those of the first and second U-shaped portions.

Because of the above-mentioned structure, a planar coil can be obtained in which the total length of each linear conductive line portion extending in the first direction F is sufficiently larger than the total length of each linear conductive line portions extending in the second direction E. In addition, in a predetermined area, the total length of each linear conductive line portion extending in the first direction F is larger than that of the other structure. The number of windings can be one, or three or more, instead of two.

The shape of the planar coil 14 can be the same as those shown in Figures 9A-9C, 10A-10C, 11A and 11B. For simplicity, these figures show planar coils including one winding on a plane. However, as shown in Figure 1, if wire bonding is used, a planar coil including two or more windings can be obtained. In addition, the number of U-shaped portions of each winding is not limited to those shown in these figures.

The magnetic layer 12b covers the main portion of the planar coil 14, as shown in Figure 1. The planar coil 14 is provided with a projected portion 17 which is not covered with the magnetic layer 12b. Over the projected portion 17, an internal end 18 of the planar coil 14 is

connected to the input/output terminal 15a with a gold wire 19 by wire bonding. Because of this, the planar coil 14 including two windings can be produced by a single photolithography process.

The planar coil 14 with the above-mentioned structure has the following two advantages.

Firstly, the magnetic layers 12a and 12b two-dimensionally formed can be effectively used as much as possible as a magnetic core of the planar coil 14. The following is generally known: Assuming that a certain distance (i.e., characteristic length) at which the magnetic flux of the magnetic layers 12a and 12b is attenuated to 1/e is λ , then $\lambda = (\mu_r g t_m / 2)$ (see, IEEE Tr. Magn. MAG14, pp. 509-511). Here, μ_r represents relative permeability of the magnetic layers 12a and 12b; g represents a gap thereof; and t_m represents a layer thickness thereof. If the above-mentioned values are substituted in this equation, $\lambda = 32 \mu\text{m}$. That is to say, the magnetic flux is attenuated to 1/e at a distance of 30 μm from each conductive line portion. This characteristic length λ is relatively small. The reason for this is that the magnetic layers 12a and 12b have a relatively small thickness (i.e., 5 μm) and have small relative permeability (i.e., 100). Since the characteristic length λ is small, even though the planar coil 14 is formed in a certain limited area as shown in Figure 1 (in which parts of the planar coil 14 are bent), the bent portions have little effect on the magnetic flux formed by the other portions of the planar coil 14. Thus, the magnetic layers 12a and 12b can be effectively used as much as possible as a magnetic core. It is preferred that the distance between the two adjacent conductive line portions in which an electric current flows in the opposite directions to each other is sufficiently larger than the characteristic length λ . The reason why the distance between the adjacent conductive line portions in which an electric current flows in the same direction is made as small as possible is to minimize the magnetic flux leaking between the conductive line portions. Since the distance between the conductive line portions in which an electric current flows in the same direction is 10 μm in this case, this value is sufficiently smaller than the characteristic length λ and thus, less magnetic flux is leaked. Because of this, the inductance of the planar coil 14 is increased in proportion to nearly the square of the number of windings.

Secondly, in a case where the planar coil 14 is formed as shown in Figure 1, the planar coil 14 can magnetize the magnetic layers 12a and 12b substantially in one direction as a whole. When stress is applied to the magnetic layers 12a and 12b having magnetostriction, magnetic anisotropy is induced in the stress direction due to magnetoelastic energy; as a result, the permeability in the stress direction is changed. Since the mechanical sensor of the present example detects the change of the permeability as the change of inductance, it is required that the magnetizing direction and the stress direction are aligned as much as possible. In a case where the conductive line and the magnetic layers

12a and 12b are formed on the substrate, the flat conductive line and the magnetic layers 12a and 12b are in parallel with each other. Because of this, the magnetizing direction is in parallel with the inner surface of the magnetic layers 12a and 12b and is orthogonal to the conductive line. In addition, since the stress generated in the magnetic layers 12a and 12b has the same magnitude as that generated on the surface of the substrate 11, it is considered that in the magnetic layers 12a and 12b, stress which is in parallel with the surface of the magnetic layers 12a and 12b is generated. Because of this, the planar coil 14 shown in Figure 1 can selectively detect only the stress which is in substantially parallel with the direction E.

Hereinafter, the operation of the mechanical sensor of the present example will be described.

When the substrate 11 is pressurized, stress and strain having components in parallel with the direction E are generated on the surface of the substrate 11 (namely, the magnetic layers 12a and 12b). Assuming that the angle formed by each line segment of the planar coil 14 and the second direction E is represented by θ , and the change of inductance of the planar coil 14 caused by the stress is represented by ΔL . ΔL is in proportion to a component of the magnetizing direction of stress generated on the surface of the substrate 11. Because of this, ΔL is represented by the following Equation (1):

$$\Delta L = k_1 \times \delta \times (R \sin \theta + S \cos \theta) \quad (1)$$

where k_1 is a proportional constant, δ is stress, R is total length of the line segments of the planar coil 14 sandwiched between the magnetic layers 12a and 12b in the direction F, and S is total length of the line segments of the planar coil 14 thereof in the direction E.

It is understood from Equation (1) that ΔL becomes maximum in a case where R/S is large and θ is close to 90°. Thus, the planar coil 14 is placed so that R/S is large and θ is close to 90°. When R/S is large, cross talk (output component caused by the stress in the direction shifted by 90° from the direction of stress generated on the surface of the substrate 11) can be minimized.

The above-mentioned conditions can be satisfied in the structure of the present example. That is, as shown in Figure 1, the planar coil 14 is bent in a rectangular wave shape and the length of the line segments extending in a certain direction is made larger than that of the other line segments extending in the other direction. In the present example, θ is set at 90°.

The distance between the adjacent conductive line portions in which an electric current flows in the opposite directions to each other is determined, considering the characteristic length λ . In a case where this distance is too large, R/S becomes small, increasing the area which is not magnetized. In contrast, in a case where this dis-

tance is too small, the inductance becomes small. In the present example, the distance between the adjacent conductive line portions in which an electric current flows in the opposite directions to each other is set at about 6 times the characteristic length λ . In the present example, R is 23000 μm and S is 1600 μm , so that R/S is 14.4.

The same effects as those obtained by using the planar coil 14 can also be obtained by using a meander coil (e.g., IEEE Tran. Magn. MAG-20, pp. 1804-1806, 1984). The meander coil has the following advantages: A step of connecting the internal end 18 to the input/output terminal 15a is not required, and the resonance frequency is increased. However, since the number of windings of the meander coil is one, the inductance is relatively low.

In the case of another planar coil for zero correction, since ΔL becomes minimum at $\theta = 0$, the planar coil is placed on the substrate 11 so that θ becomes 0. In addition, since the minimum value of ΔL is in proportion to S, it is preferred that R/S is large.

Example 2

Figure 4 is a perspective view showing the structure of another mechanical sensor according to the present invention. Figure 5 is a cross-sectional view taken along a line G-G' of Figure 4.

A substrate 21 has an insulating property at least on the surface thereof. The substrate 21 has a longitudinal side of 30 mm, a vertical side of 15 mm, and a thickness of 0.5 mm. On the substrate 21, a conductive line 22 made of an aluminum film with a thickness of 4 μm is formed. The conductive line 22 winds around a magnetic layer 24 covered with an insulator layer 23 in a solenoidal shape. Thus, the conductive line 22 forms a solenoidal coil. A thin portion of the insulator layer 23 has a thickness of 2 μm , and a thick portion thereof is 7 μm . As shown in Figure 5, an insulator layer 25 is formed between the respective portions (which are in contact with the respective portions (which are in contact with the substrate 21) of the conductive line 22, the insulator layer 25 having the same thickness as that of the conductive line 22. The magnetic layer 24 is made of an Fe based amorphous film (thickness: 5 μm) formed by a sputtering method. The magnetic layer 24 has a rectangular shape (2000 μm x 3000 μm). The relative permeability and magnetostriction constant of the magnetic layer 24 at a frequency of 1 MHz are 100 and +22 ppm, respectively.

The portions of the conductive line 22 positioned above and below the magnetic layer 24 extend in the direction orthogonal to the longitudinal direction (hereinafter, this longitudinal direction is referred to as a direction H) of the magnetic layer 24. The reason for this is that the conductive line 22 magnetizes the magnetic layer 24 in the direction H. The portions (bent portions) of the conductive line 22 connecting the portions of the

conductive line 22 positioned above the magnetic layer 24 with the portions of the conductive line 22 positioned below the magnetic layer 24 are not in parallel with the direction orthogonal to the direction H, as shown in Figure 4. Thus, the bent portions magnetize the magnetic layer 24 in the direction shifted from the direction H. However, since the magnetic layer 24 is not present in the vicinity of the bent portions of the conductive line 22, the magnetic flux generated by the bent portions hardly influences the magnetic layer 24. In Figure 4, for making it easy to see the conductive line 22, the insulator layer 25 is omitted.

Next, the operation of the mechanical sensor of the present example will be described.

Assuming that stress is generated in the longitudinal direction (I direction) of the substrate 21. In the present example, the conductive line 22 magnetizes the magnetic layer 24 in the direction H, so that the change of inductance due to the stress can be represented by the following Equation (2):

$$\Delta L = k_2 \times \delta \cos \theta \quad (2)$$

where ΔL is the change of inductance, k_2 is a proportional constant, δ is applied stress, and θ is an angle formed by the directions H and I. As is apparent from Equation (2), when θ is 0° , ΔL becomes maximum; and when θ is 90° , ΔL becomes 0. In the present example, θ is set at 0° , so that ΔL becomes maximum. In addition, from Equation (2), ΔL is almost 0 in a case where θ is shifted by 90° in the present example. Thus, in this case, the cross talk becomes minimum.

In a case where a coil for zero correction is used, it is preferred that θ is set at 90° .

Even though the magnetic layer having magnetostriction extends to the vicinity of the bent portions of the conductive line 22, the mechanical sensor is still effective. In this case, ΔL and cross talk are somewhat increased.

Example 3

Figure 6 is a plan view showing the structure of still another mechanical sensor of the present invention. Figure 7 is a cross-sectional view taken along a line J-J' of Figure 6, and Figure 8 is a cross-sectional view taken along a line K-K' of Figure 6.

A substrate 31 has a longitudinal side of 30 mm, a vertical side of 15 mm, and a thickness of 0.5 mm. On the substrate 31, magnetic layers 32a and 32b made of an Fe based amorphous film having a thickness of 5 μm are formed. The magnetic layers 32a and 32b are formed by, for example, a sputtering method. The relative permeability and magnetostriction constant of the magnetic layers 32a and 32b at a frequency of 1 MHz are 100 and +22 ppm, respectively. An insulator layer

33a is made of SiO_2 having a thickness of 2 μm , and an insulator layer 33b is made of SiO_2 having a thickness of 2 to 7 μm . On the insulator layer 33a, a planar coil 34 made of an aluminum film having a thickness of 5 μm and input/output terminals 35a and 35b are formed. The respective shapes of the planar coil 34 and the input/output terminals 35a and 35b are the same as those of the planar coil 14 and the input/output terminals 15a and 15b as shown in Figure 1. An insulator layer 36 having the same thickness as that of the planar coil 34 fills between the conductive line portions in which an electric current flows in the same direction. An internal end 38 of the planar coil 34 is connected to the input/output terminal 35a via a gold wire 39.

For convenience, in Figure 6, only the planar coil 34 can be seen below the magnetic layer 32b.

The structure of the mechanical sensor of the present example is basically the same as that of the mechanical sensor as shown in Figure 1. The difference therebetween is that in the present example, the magnetic layers 32a and 32b are formed so that the magnetic layers 32a and 32b do not overlap the portions of the planar coil 34 extending in a vertical direction N thereof but overlap the portions of the planar coil 34 extending in a longitudinal direction M thereof. The size of the magnetic layers 32a and 32b is as follows: P is 2400 μm and Q is 1000 μm .

Next, the operation of the mechanical sensor of the present example will be described.

Assuming that the longitudinal direction of the substrate 31 is in the direction N, stress is applied in the direction N, an angle formed by the directions M and N is θ , and the change of inductance is ΔL . If $R = (2400 \times 8)/23000 \approx 0.8R$ and $S = 0$ is substituted in Equation (1), ΔL can be represented by Equation (3):

$$\Delta L = k_1 \times \delta \times 0.8 \times R \sin \theta \quad (3)$$

As is apparent from Equation (3), when θ is 90° , ΔL becomes maximum, and when θ is 0° , ΔL becomes 0. In the present example, θ is set at 90° .

Compared with Example 1, ΔL is smaller by about 20%. However, when θ is shifted by 90° , ΔL becomes 0, so that the cross talk becomes almost 0. In this respect, the mechanical sensor of the present example is more excellent than that of Figure 1. In a case where a coil for zero correction is formed at $\theta = 0$, the small cross talk has favorable effects.

In addition, the same structure as that of the present example can be realized by using a meander coil.

In Examples 1 to 3, an Fe based amorphous film having a positive magnetostriction constant, formed by a sputtering method is used as a magnetic layer having magnetostriction. However, any materials having magnetostriction can be used for a magnetic layer. For example, even a magnetic layer having negative magne-

tostriction can be used in the structures of the present invention.

Moreover, in Examples 1 to 3, only magnetic layers having magnetostriction are used. However, a magnetic layer having a magnetostriction of almost 0 and high relative permeability can be used as a part of the magnetic circuit.

According to the present invention, a small and thin mechanical sensor is provided. The mechanical sensor of the present invention effectively uses a magnetic layer which is thinner than the bulk, so that the mechanical sensor of the present invention has high sensitivity for detection irrespective of its thinness. Moreover, the mechanical sensor of the present invention can selectively detect the level of stress in a certain direction with high sensitivity, based on the anisotropy of the sensitivity for detection which does not depend upon the shape of the magnetic layer.

Various other modifications will be apparent to and can be readily made by those skilled in the art without departing from the scope of this invention as claimed.

Claims

1. A mechanical sensor comprising:

- a magnetic layer (12a, 12b; 24; 32a, 32b) having a permeability which is changed in accordance with stress generated therein;
- a coil (14; 22; 34) having at least two terminals (15a, 15b; 35a, 35b), allowing an electric current to flow therebetween to generate a magnetic flux, thereby magnetizing the magnetic layer (12a, 12b; 24; 32a, 32b);
- a substrate (11; 21; 31) integrally supporting the magnetic layer (12a, 12b; 24; 32a, 32b) and the coil (14; 22; 34)
- wherein the coil (14; 22; 34) is a planar coil including at least one winding, each winding having a U-shaped portion formed of a first conductive line portion (14a, 14d) a second conductive line portion (14b, 14c), and a connecting portion connecting the first and second conductive line portions (14a - 14d), the first and second conductive line portions (14a - 14d) extending in a first direction (F; M), the connecting portion extending in a second direction (E; N) being vertical to the first direction (F; M), and impedance between the terminals (15a, 15b; 35a, 35b) is changed in accordance with a change of inductance caused by a change of the permeability of the magnetic layer (12a, 12b; 24; 32a, 32b);

characterized in that

the total length of each linear conductive line

portion extending in the first direction (F; M) is larger than the total length of each linear conductive line portion extending in the second direction (E; N); and

the magnetic layer (12a, 12b; 24; 32a, 32b) is magnetized substantially in a direction orthogonal to the first direction (F; M).

2. A mechanical sensor according to claim 1, wherein a distance between conductive line portions in which an electric current flows in the same direction is smaller than a distance between conductive line portions in which an electric current flows in the opposite directions to each other.
3. A mechanical sensor according to claim 1 or 2, wherein the coil (14; 22; 34) is formed on an insulator layer (13a; 23; 33a) supported by the substrate (11; 21; 31).
4. A mechanical sensor according to one of the preceding claims, wherein the magnetic layer (12a; 33a) is formed between the insulator layer (13a; 33a) and the substrate (11; 31).
5. A mechanical sensor according to one of the preceding claims, wherein the magnetic layer (12b; 24; 32b) is formed on the coil (14; 22; 34) with another insulator layer (13b; 23; 33b) formed therebetween.
6. A mechanical sensor according to one of the preceding claims, wherein the magnetic layer (12; 32) has a two-layered structure (12a, 12b; 32a, 32b) and sandwiches the coil (14; 34).
7. A mechanical sensor according to one of the preceding claims comprising:
 - a second U-shaped portion formed of a third conductive line portion (14e, 14h), a fourth conductive line portion (14f, 14g), and a connecting portion connecting the third and fourth conductive line portion (14e - 14h) the first, second, third, and fourth conductive line portions (14a - 14h) extending in the first direction (E; M),
 - wherein the first and second U-shaped portions are connected in series between the terminals (15a, 15b).

Patentansprüche

1. Mechanischer Sensor mit:

einer magnetischen Schicht (12a, 12b; 24; 32a, 32b) mit einer Permeabilität, welche in Abhängigkeit von einer darin erzeugten Belastung bzw. Deformation bzw. Dehnung bzw. Span-

nung verändert wird;
einer Spule (14; 22; 34) mit mindestens zwei
Anschlüssen (15a, 15b; 35a, 35b), welche es
einem elektrischen Strom ermöglichen dazwi-
schen zu fließen um einen magnetischen Fluß
zu erzeugen, wodurch die magnetische Schicht
(12a, 12b; 24; 32a, 32b) magnetisiert wird;
einem Substrat (11; 21; 31), welches einteilig
bzw. integral die magnetische Schicht (12a,
12b; 24; 32a, 32b) und die Spule (14; 22; 34)
stützt bzw. trägt;

wobei die Spule (14; 22; 34) eine planare bzw.
ebene bzw. flache Spule ist, welche minde-
stens eine Wicklung bzw. Windung umfaßt, wo-
bei jede Wicklung einen U-förmigen Abschnitt
aufweist, welcher aus einem ersten leitfähigen
Leitungsabschnitt (14a, 14d), einem zweiten
leitfähigen Leitungsabschnitt (14b, 14c), und
einem Verbindungsabschnitt, welcher die er-
sten und zweiten leitfähigen Leitungsabschnit-
te (14a - 14d) verbindet, gebildet ist, wobei sich
die ersten und zweiten leitfähigen Leitungsab-
schnitte (14a - 14d) in einer ersten Richtung (F;
M) erstrecken, sich der Verbindungsabschnitt
in eine zweite Richtung (E; N) erstreckt, welche
senkrecht zur ersten Richtung (F; M) ist, und
eine Impedanz zwischen den Anschlüssen
(15a, 15b; 35a, 35b) in Abhängigkeit von einer
Veränderung der Induktivität verändert wird,
welche durch eine Veränderung der Permeabi-
lität der magnetischen Schicht (12a, 12b; 24;
32a, 32b) verursacht wird;

dadurch gekennzeichnet, daß

die gesamte Länge eines jeden linearen leitfä-
higen Leitungsabschnitts, welcher sich in die
erste Richtung (F; M) erstreckt, größer ist, als
die gesamte Länge eines jeden linearen leitfä-
higen Leitungsabschnitts, welcher sich in die
zweite Richtung (E; N) erstreckt; und
die magnetische Schicht (12a, 12b; 24; 32a,
32b) im wesentlichen in einer Richtung magne-
tisiert wird, die senkrecht zu der ersten Rich-
tung (F; M) ist.

2. Mechanischer Sensor nach Anspruch 1, wobei der
Abstand zwischen den leitfähigen Leitungsab-
schnitten, in welchen ein elektrischer Strom in die
gleiche Richtung fließt, geringer ist als der Abstand
zwischen den leitfähigen Leitungsabschnitten, in
welchen ein elektrischer Strom in entgegengesetz-
te Richtungen zueinander fließt.
3. Mechanischer Sensor nach Anspruch 1 oder 2, wo-
bei die Spule (14; 22; 34) aus einer Isolations-
schicht (13a; 23; 33a) gebildet wird, welche vom
Substrat (11; 21; 31) gestützt bzw. getragen wird.

4. Mechanischer Sensor nach einem der vorherge-
henden Ansprüche, wobei die magnetische Schicht
(12a; 32a) zwischen der Isolationsschicht (13a;
33a) und dem Substrat (11; 31) ausgebildet ist.

5. Mechanischer Sensor nach einem der vorherge-
henden Ansprüche, wobei die magnetische Schicht
(12a, 24; 32b) auf der Spule (14; 22; 34) ausgebildet
ist mit einer anderen Isolationsschicht (13b; 23;
33b), welche dazwischen ausgebildet ist.

6. Mechanischer Sensor nach einem der vorherge-
henden Ansprüche, wobei die magnetische Schicht
(12; 32) eine zweischichtige Struktur (12a, 12b;
32a, 32b) aufweist und die Spule (14; 34) zwischen
sich aufnimmt.

7. Mechanischer Sensor nach einem der vorherge-
henden Ansprüche mit:

einem zweiten U-förmigen Abschnitt, welcher
aus einem dritten leitfähigen Leitungsabschnitt
(14e, 14h), einem vierten leitfähigen Leitungs-
abschnitt (14f, 14g), und einem Verbindungs-
abschnitt gebildet wird, welcher den dritten und
vierten leitfähigen Leitungsabschnitt (14e -
14h) verbindet, wobei sich die ersten, zweiten,
dritten und vierten leitfähigen Leitungsab-
schnitte (14a - 14h) in die erste Richtung (E; M)
erstrecken,
wobei die ersten und zweiten U-förmigen Ab-
schnitte in Serie zwischen den Anschlüssen
(15a, 15b) geschaltet sind.

Revendications

1. Capteur mécanique comportant :

une couche magnétique (12a, 12b; 24; 32a,
32b) comportant une perméabilité qui est mo-
difiée selon la pression générée dessus;
une bobine (14; 22; 34) comportant au moins
deux bornes (15a, 15b; 35a, 35b), permettant
à un courant électrique de circuler entre elles
pour générer un flux magnétique, magnétisant
la couche magnétique (12a, 12b; 24; 32a, 32b);
un substrat (11; 21; 31) supportant intégrale-
ment la couche magnétique (12a, 12b; 24; 32a,
32b) et la bobine (14; 22; 34);
dans lequel la bobine (14; 22; 34) est une bo-
bine plane comportant au moins un enroule-
ment, chaque enroulement comportant une
partie en forme de U formée d'une première
partie de ligne conductrice (14a, 14d), une se-
conde partie de ligne conductrice (14b, 14c), et
une partie de connexion connectant les premiè-
re et seconde parties de ligne conductrice (14a

- 14d), les première et seconde parties de ligne conductrice (14a - 14d) s'étendant dans une première direction (F; M), la partie de connexion s'étendant dans une seconde direction (E; N) verticale à la première direction (F; M), et l'impédance entre les bornes (15a, 15b; 35a, 35b) est modifiée selon un changement de l'inductance causée par un changement de la perméabilité de la couche magnétique (12a, 12b; 24; 32a, 32b);

caractérisé en ce que

la longueur totale de chaque partie de ligne conductrice linéaire s'étendant dans la première direction (F; M) est plus grande que la longueur totale de chaque partie de ligne conductrice linéaire s'étendant dans la seconde direction (E; N); et

la couche magnétique (12a, 12b; 24; 32a, 32b) est aimantée pour l'essentiel dans une direction orthogonale à la première direction (F; M).

2. Capteur mécanique selon la revendication 1, dans lequel une distance entre des parties de ligne conductrice dans lesquelles un courant électrique circule dans la même direction est plus petite qu'une distance entre des parties de lignes conductrices dans lesquelles un courant électrique circule dans les directions opposées les unes aux autres.
3. Capteur mécanique selon la revendication 1 ou 2, dans lequel la bobine (14; 22; 34) est formée sur une couche isolante (13a; 23; 33a) supportée par le substrat (11; 21; 31).
4. Capteur mécanique selon l'une quelconque des revendications précédentes, dans lequel la couche magnétique (12a; 33a) est formée entre la couche isolante (13a; 33a) et le substrat (11; 31).
5. Capteur mécanique selon l'une quelconque des revendications précédentes, dans lequel la couche magnétique (12a; 24; 32b) est formée sur la bobine (14; 22; 34) avec une autre couche isolante (13b; 23; 33b) formée entre les deux.
6. Capteur mécanique selon l'une quelconque des revendications précédentes, dans lequel la couche magnétique (12; 32) comporte une structure à deux couches (12a, 12b; 32a, 32b) et prend en sandwich la bobine (14; 34).
7. Capteur mécanique selon l'une quelconque des revendications précédentes, comportant :

une seconde partie en forme de U formée sur une troisième partie de ligne conductrice (14e,

14h), une quatrième partie de ligne conductrice (14f, 14g), et une partie de connexion connectant la première et la quatrième partie de ligne conductrice (14e - 14h), les première, seconde, troisième et quatrième parties de ligne conductrice (14a - 14h) s'étendant dans la première direction (E; M), dans lequel les première et seconde parties en forme de U sont connectées en série entre les bornes (15a, 15b).

Fig. 1

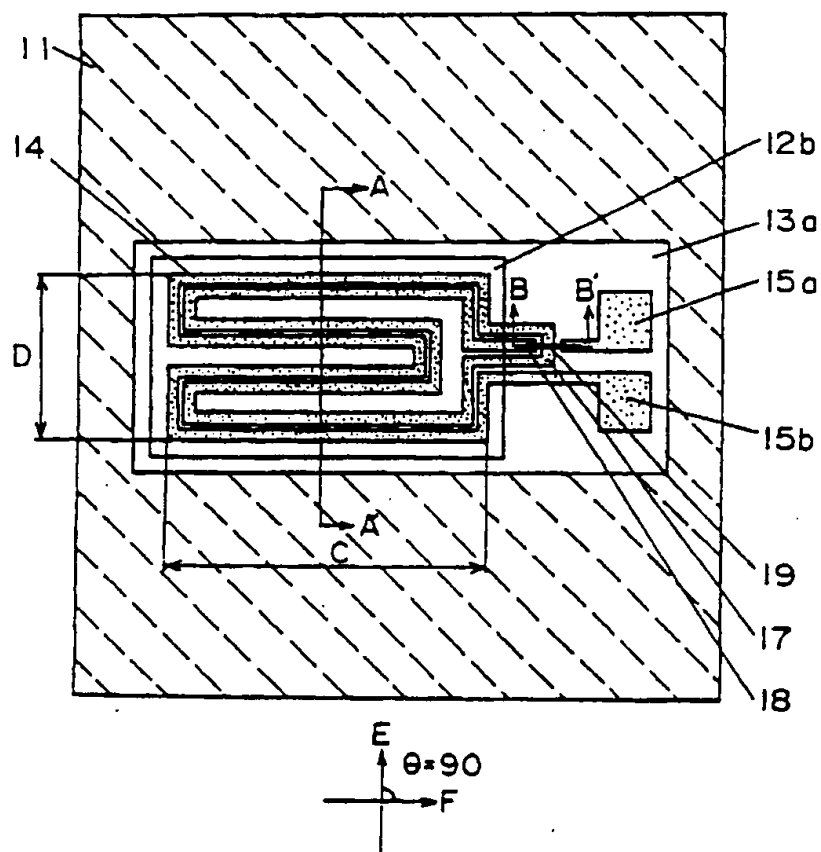


Fig. 2

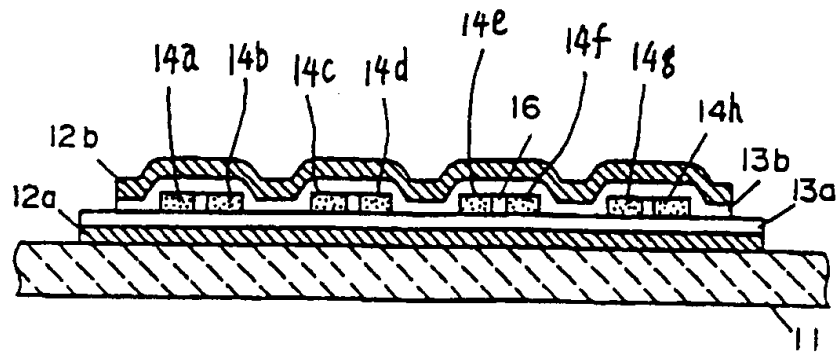


Fig. 3

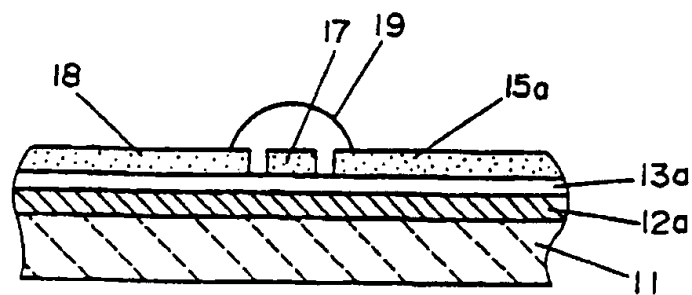


Fig. 4

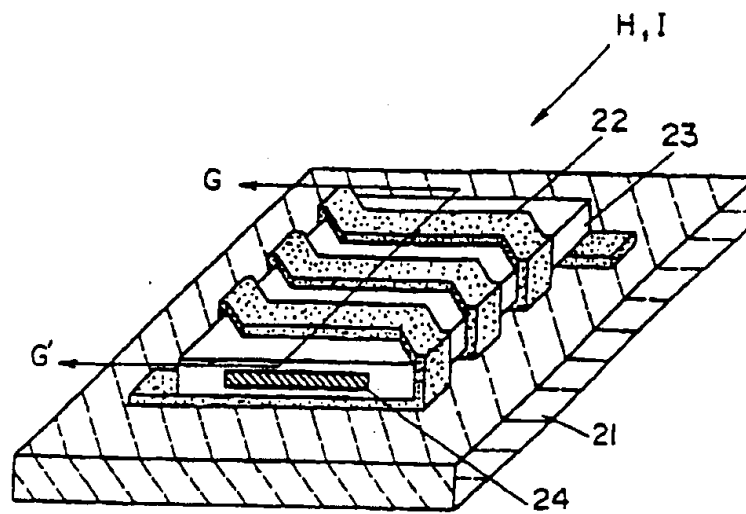


Fig. 5

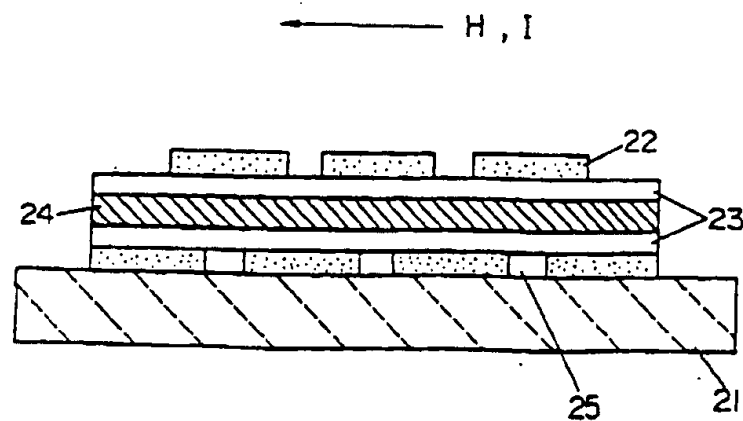


Fig. 6

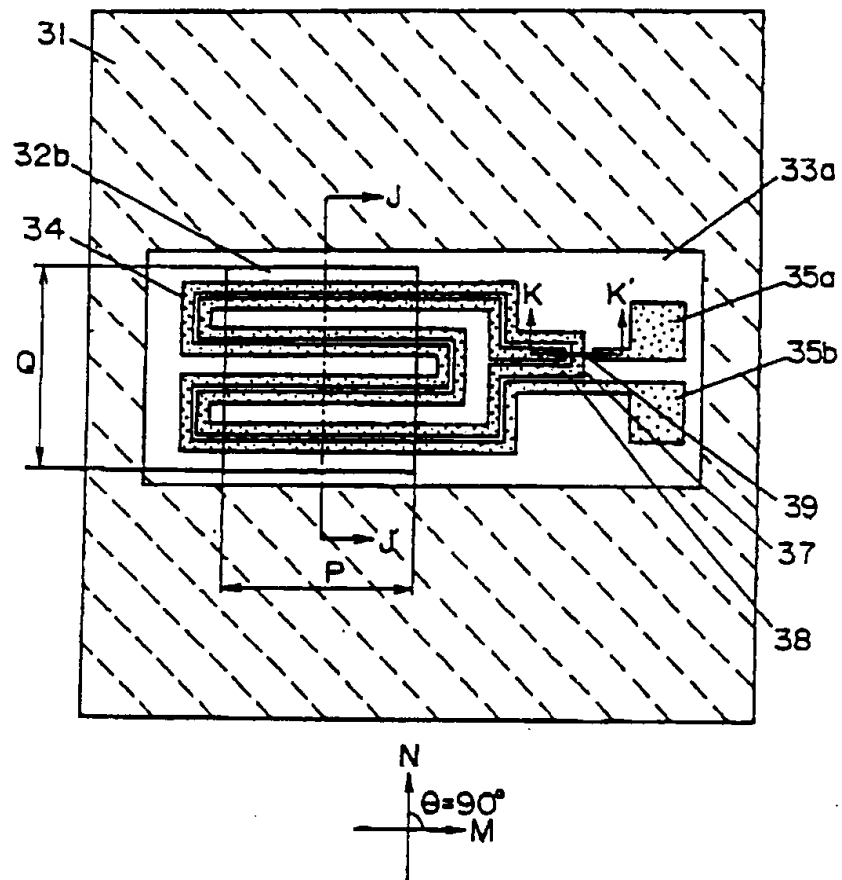


Fig. 7

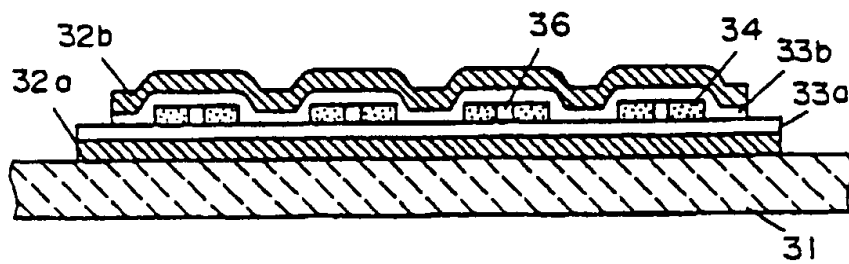


Fig. 8

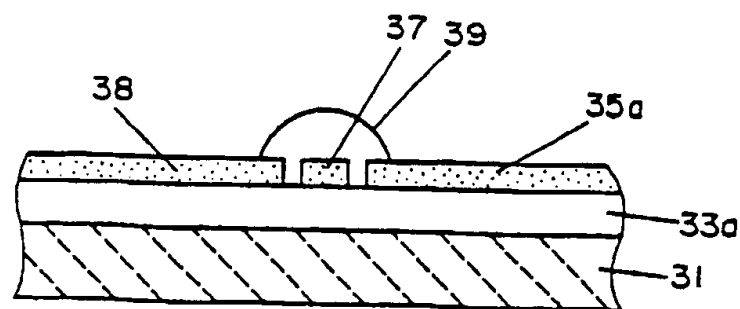


Fig. 9A

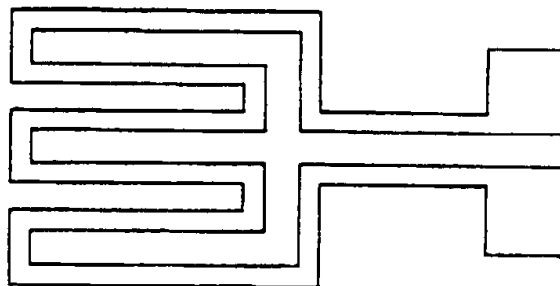


Fig. 9B

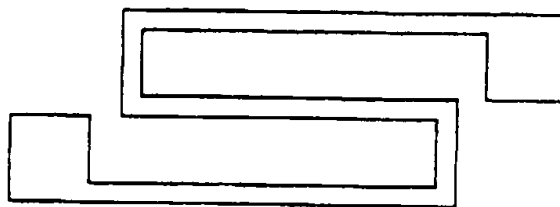


Fig. 9C

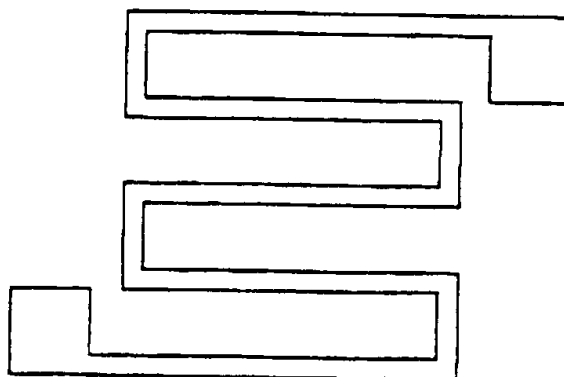


Fig.10A

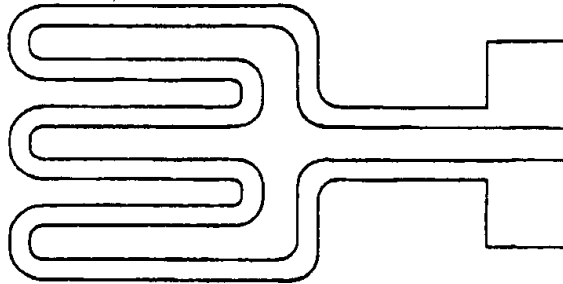


Fig.10B

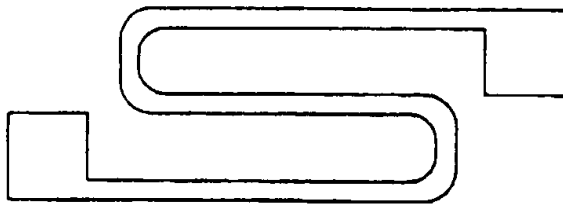


Fig.10C

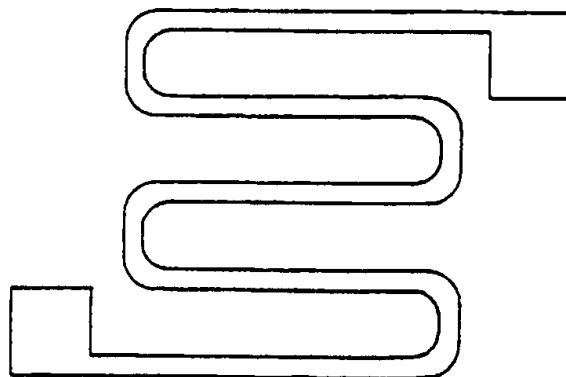


Fig.11A

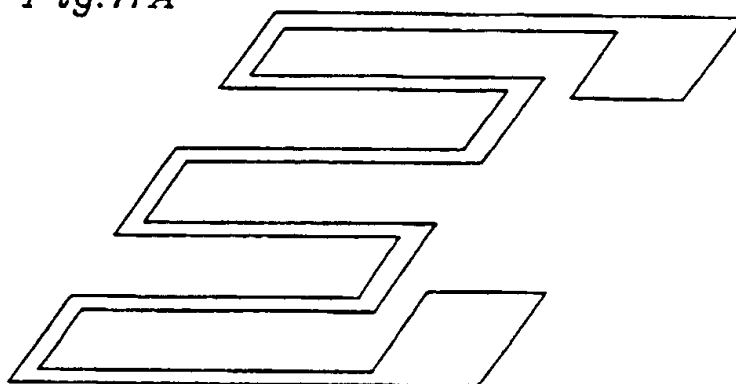


Fig.11B

